

# Introduction of $\mu m$ - and $nm$ -sized Semiconductor Raman scattering

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Oct. 4 2002

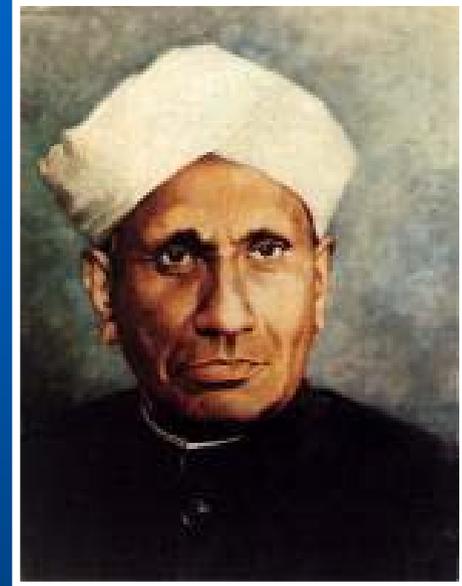
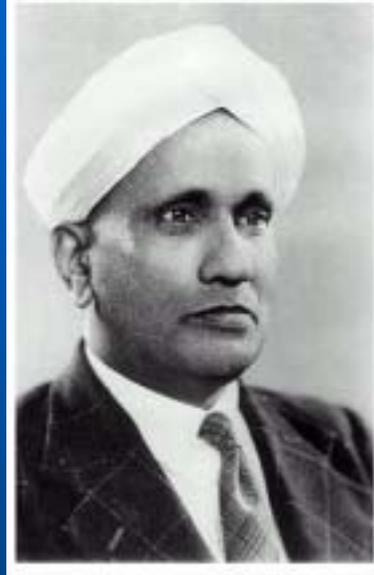


# Outline

- Introduction Semiconductor Raman Scattering
- Example: Strain and Concentrations
- Raman Scattering of Nano-Sized Semiconductor (Dot, Wire and Layers)
- Summary



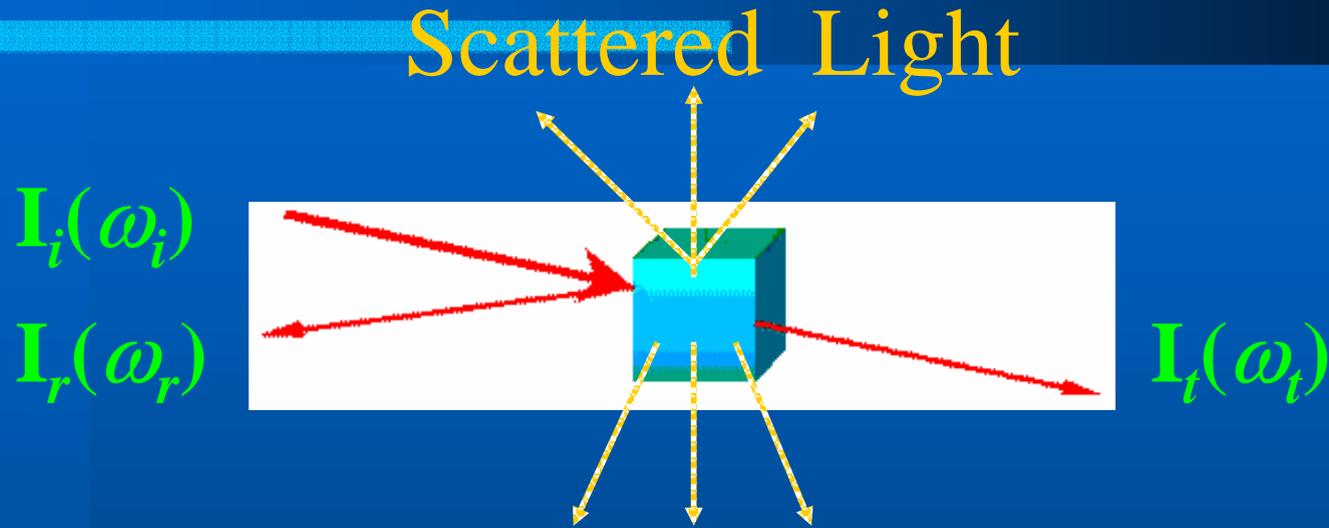
# What is Raman?



- Sir Chandrasekhara Venkata Raman
- 1930 Nobel Price Winner



# What is Light Scattering?



Mie Scattering: Particles,

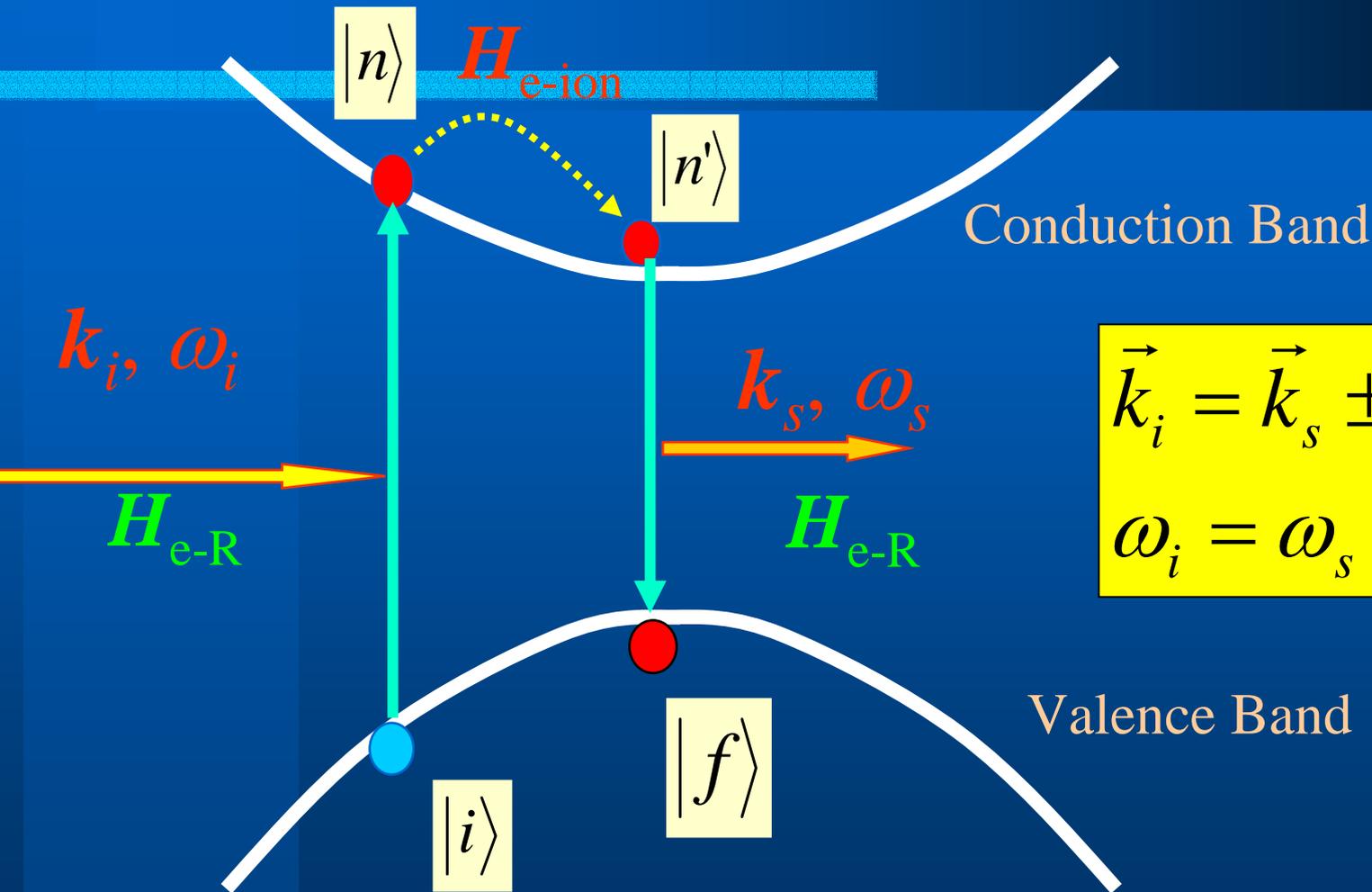
Rayleigh Scattering: Particles  $(10^{-2} \sim 10^{-3})I_i$

Brillouin Scattering: Acoustic Phonon  $(10^{-6} \sim 10^{-9})I_i$

Raman Scattering: Optical Phonon  $(10^{-6} \sim 10^{-9})I_i$



# Quantum Mechanics Picture:



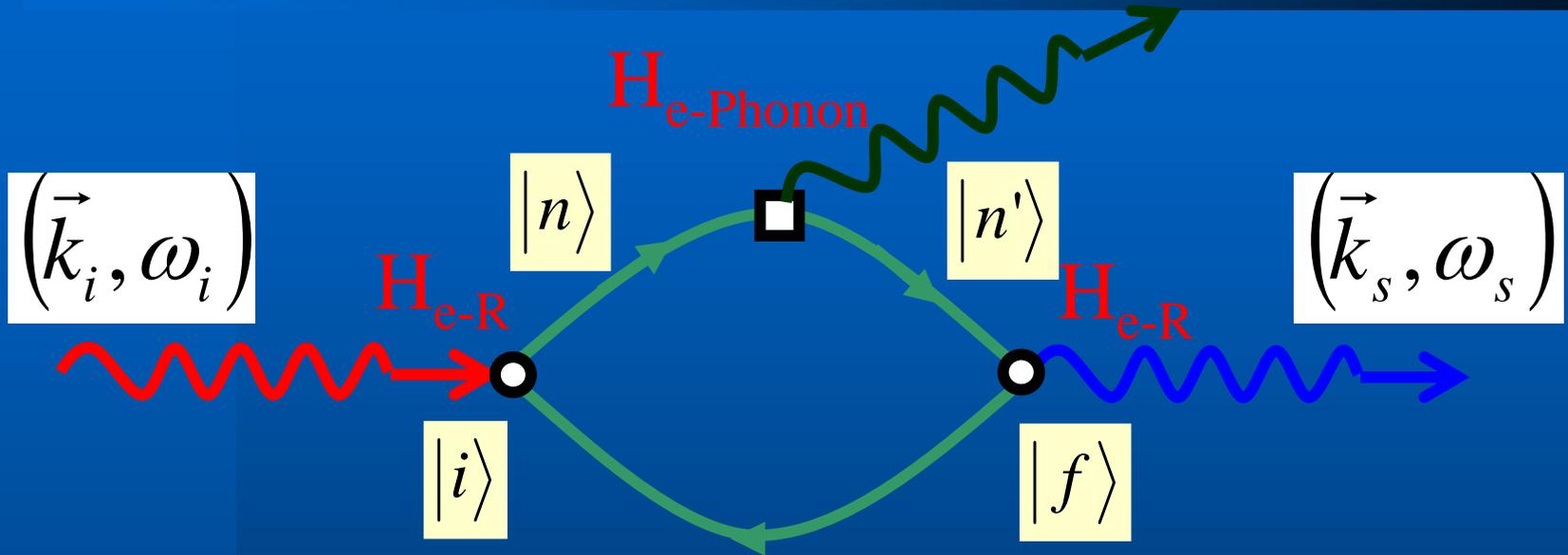
$$\vec{k}_i = \vec{k}_s \pm \vec{q}_{Phonon}$$

$$\omega_i = \omega_s \pm \omega_{Phonon}$$



# Feynmann Diagram:

$$(\vec{q}_{\text{Phonon}}, \omega_{\text{Phonon}})$$



$$\frac{d^2\sigma}{d\Omega d\omega} \propto \left| \sum_{n,n'} \frac{\langle f | H_{e-R} | n' \rangle \langle n' | H_{e-Phonon} | n \rangle \langle n | H_{e-R} | i \rangle}{(\hbar\omega_s - E_{n'} + i\Gamma_{n'}) (\hbar\omega_i - E_n + i\Gamma_n)} \right|^2$$



# Raman Lineshapes:

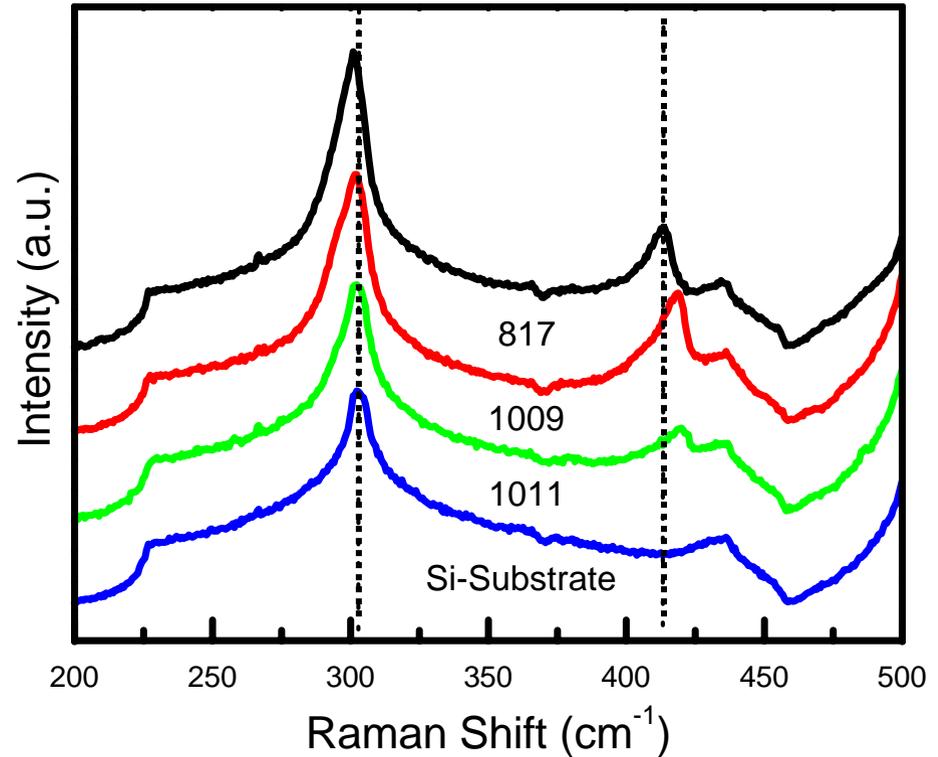
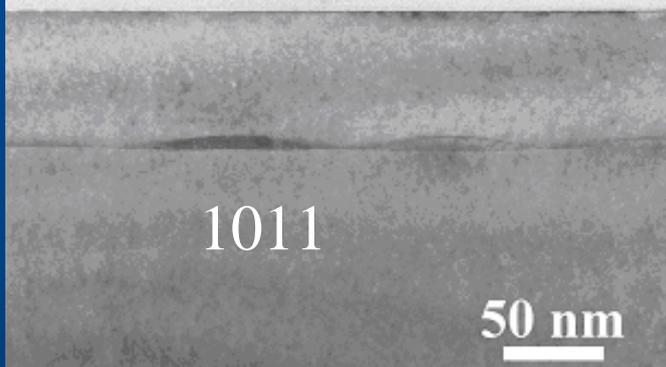
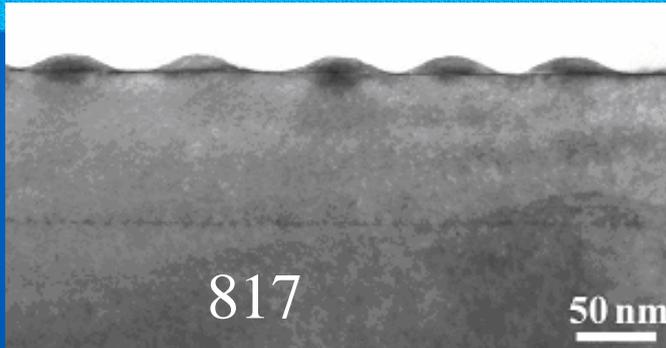
- Gaussian
- Lorentzian
- Fano
- Asymmetry
- ???

1. Raman Shift
2. Linewidth

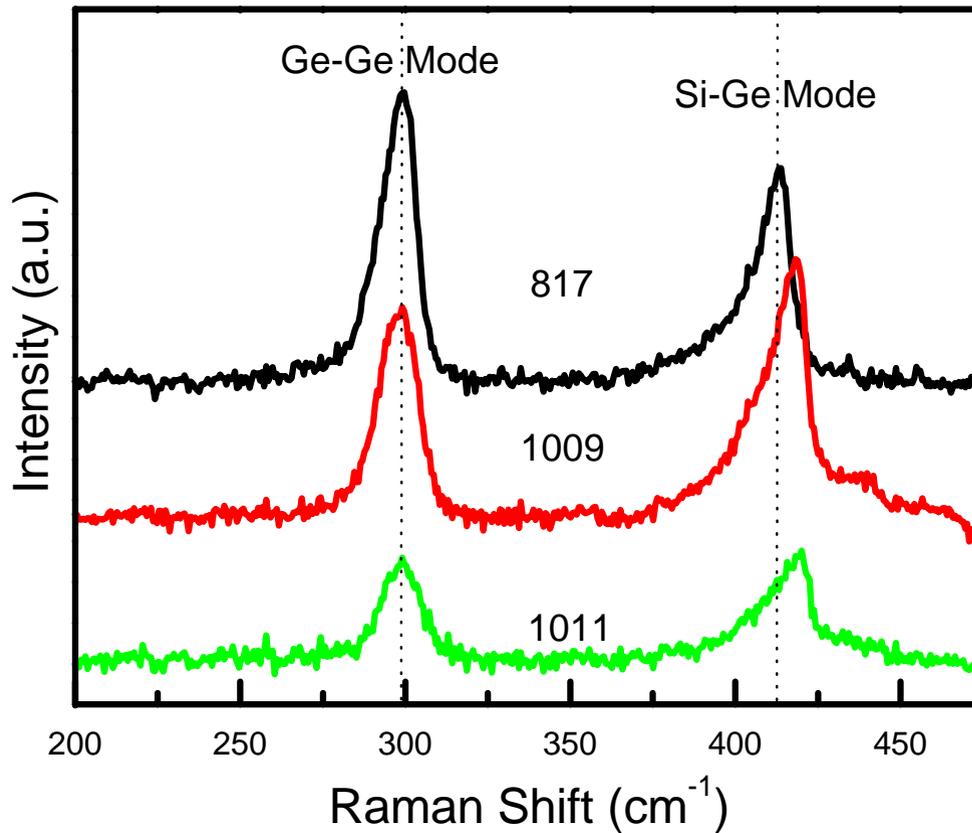
$$\frac{d^2\sigma}{d\Omega d\omega} \propto \left| \sum_{n,n'} \frac{\langle f | H_{e-R} | n' \rangle \langle n' | H_{e-Phonon} | n \rangle \langle n | H_{e-R} | i \rangle}{(\hbar\omega_s - E_{n'} + i\Gamma_{n'}) (\hbar\omega_i - E_n + i\Gamma_n)} \right|^2$$



# SiGe Alloy Dot on Si(001)



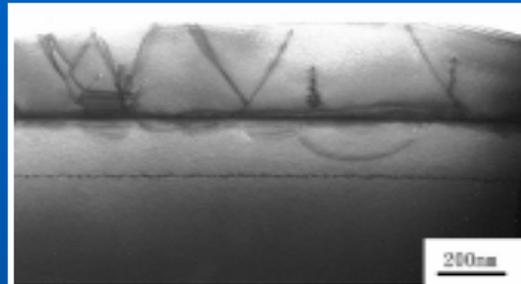
# Strain in Embedded Layer



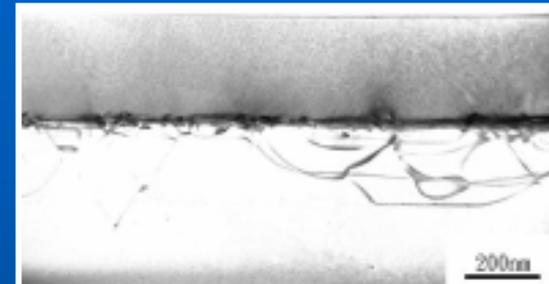
# MBE Grown Relaxed SiGe alloy



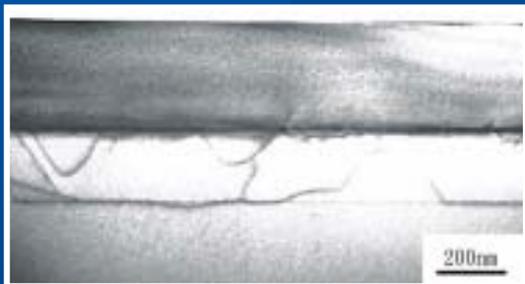
LT-Si 600 °C (# 319)



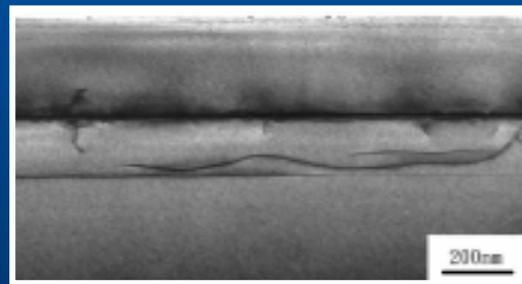
LT-Si 550 °C (# 320)



LT-Si 500 °C (# 323)



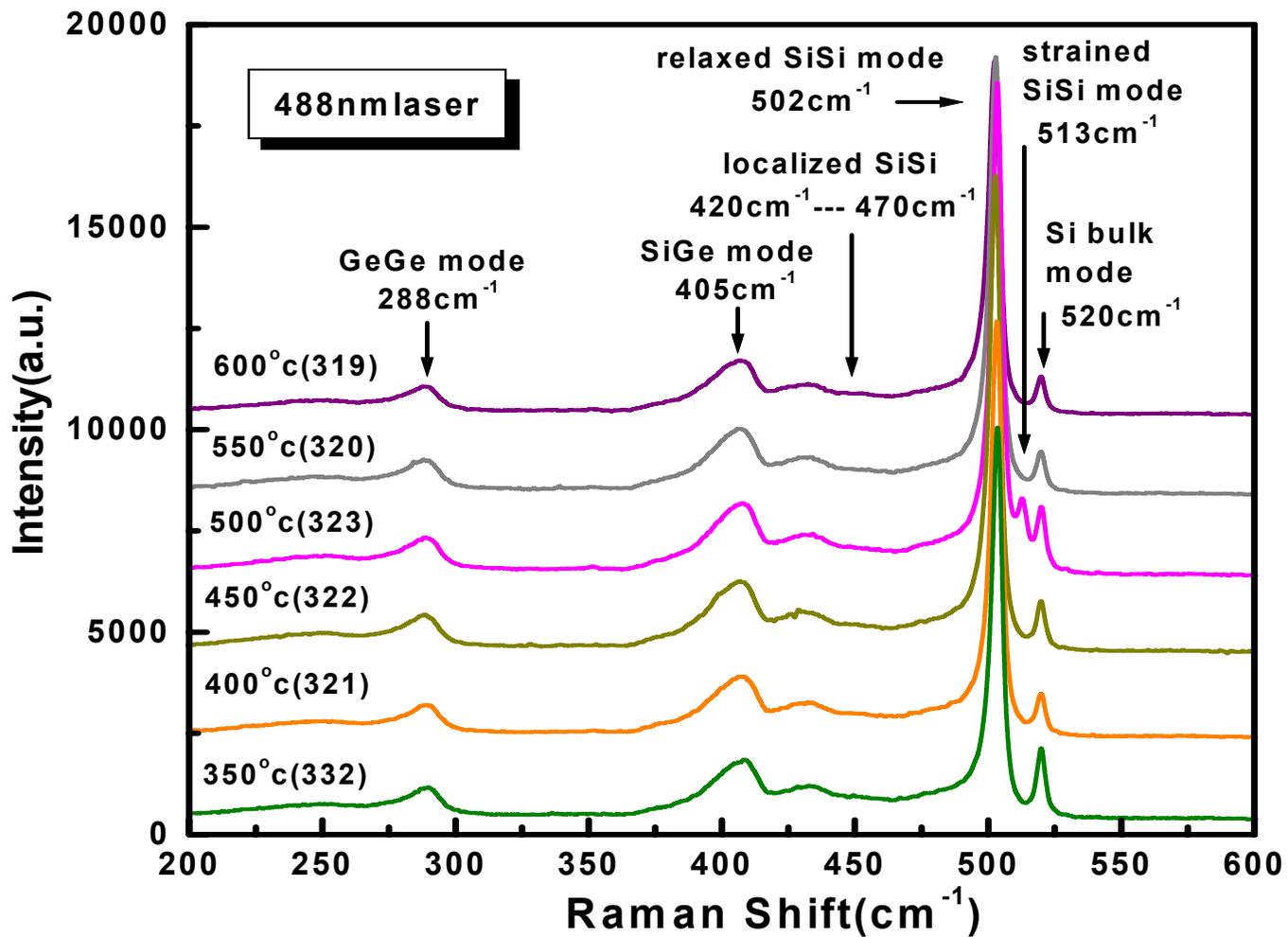
LT-Si 450 °C (# 322)



LT-Si 400 °C (# 321)

TEM圖由台大凝態中心  
鄭鴻祥教授提供





# Strain & Ge Content of Alloy

Raman Shift of  $\text{Si}_{1-x}\text{Ge}_x$  Alloy for  $x < 0.4$  :

$$\omega_{\text{SiSi}} = 520.5 - 62x - 815\varepsilon$$

$$\omega_{\text{SiGe}} = 400.5 + 14.2x - 575\varepsilon$$

$$\omega_{\text{GeGe}} = 282.5 + 16x - 385\varepsilon$$

$$\varepsilon = \delta l / l$$

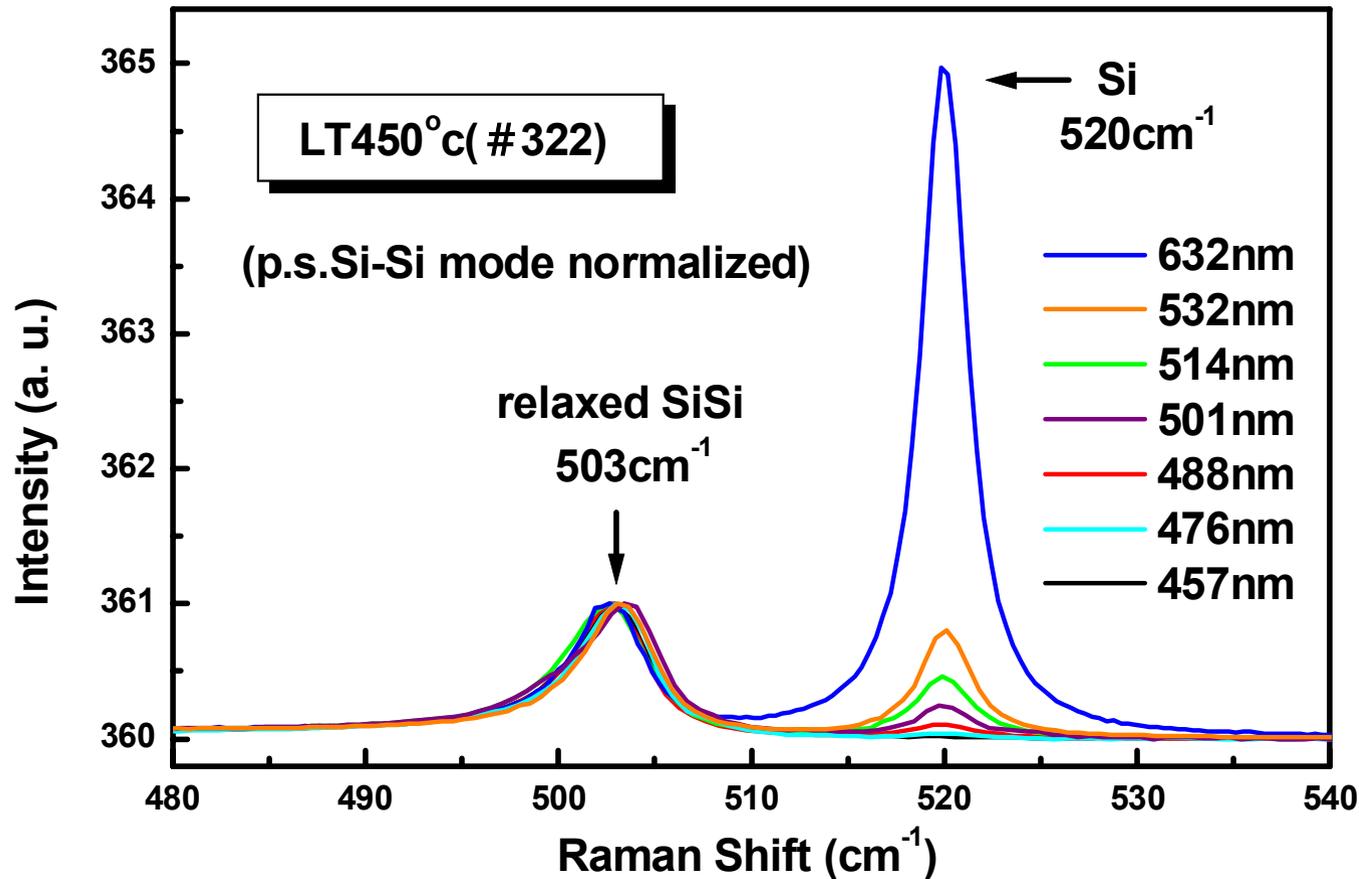


	457nm		488nm		514nm	
sample	$x$	(%)	$x$	(%)	$x$	(%)
# 319 (LT600°C)	0.3 ±0.03	-2.1 ±0.06	0.3 ±0.03	-1.9 ±0.06	0.3 ±0.02	-0.04 ±0.003
# 320 (LT550°C)	0.3 ±0.03	-2.3 ±0.06	0.3 ±0.02	-2.1 ±0.03	0.3 ±0.02	-0.7 ±0.003
# 323 (LT500°C)	0.3 ±0.03	-1.6 ±0.06	0.3 ±0.02	-1.4 ±0.03	0.3 ±0.02	-1.6 ±0.003
# 322 (LT450°C)	0.3 ±0.03	-0.7 ±0.06	0.3 ±0.03	-1.4 ±0.06	0.3 ±0.03	-3.1 ±0.006
# 321 (LT400°C)	0.3 ±0.03	-2.3 ±0.06	0.3 ±0.03	-1.6 ±0.06	0.3 ±0.02	-2.1 ±0.003
# 332 (LT350°C)	0.3 ±0.03	-1.6 ±0.06	0.3 ±0.03	-1.4 ±0.06	0.3 ±0.03	-2.6 ±0.006

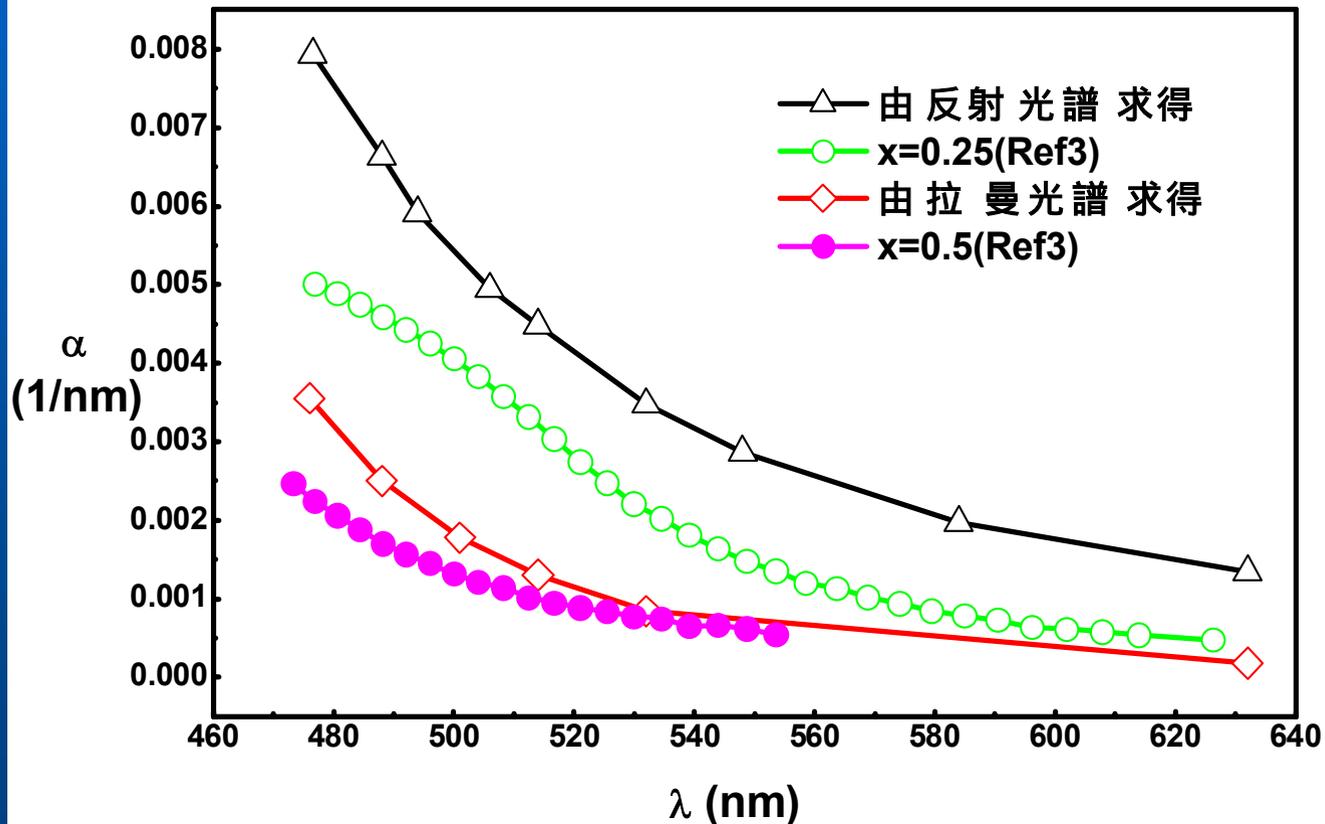
Results:  $x = 0.30$ ,  $\Sigma = -0.16\%$



# Spectra excited by various Energies



# Absorption Coefficient



# GeSi/Si Micro-Horns

Si cap	2nm
$\text{Ge}_{0.1}\text{Si}_{0.9}$	25nm
$\text{Ge}_{0.4}\text{Si}_{0.6}$	20nm
Si buffer	100nm
Si substrate	

Fig.1 sample before etching

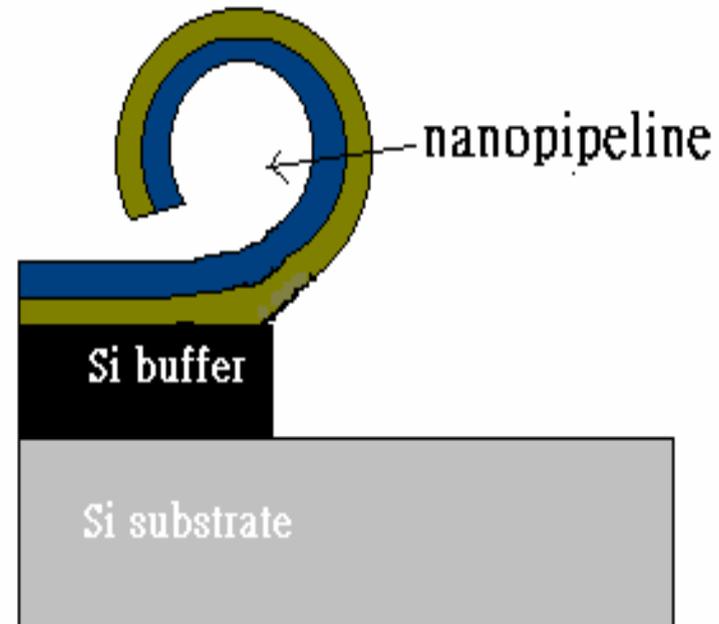
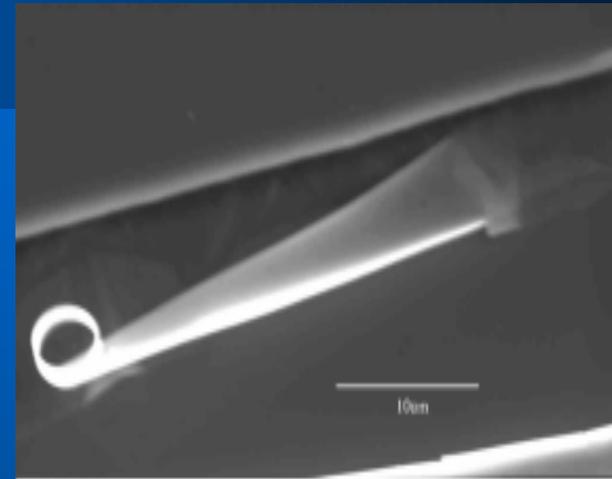


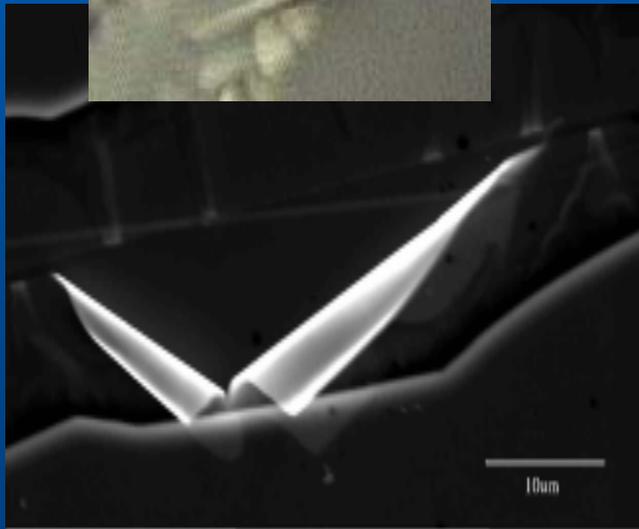
Fig.3 nanopipeline has formed



# Micro-Horn Images



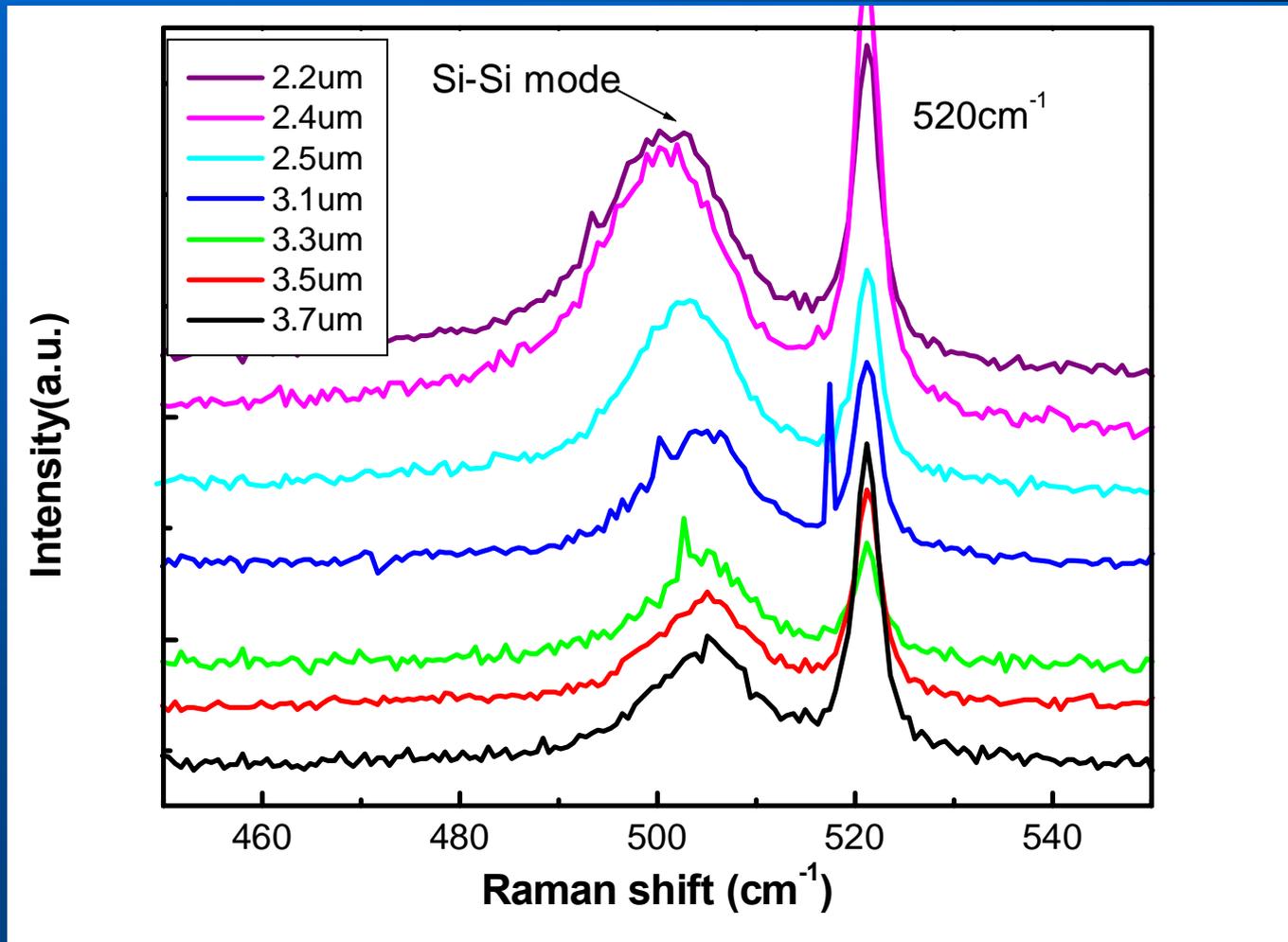
Sample 725



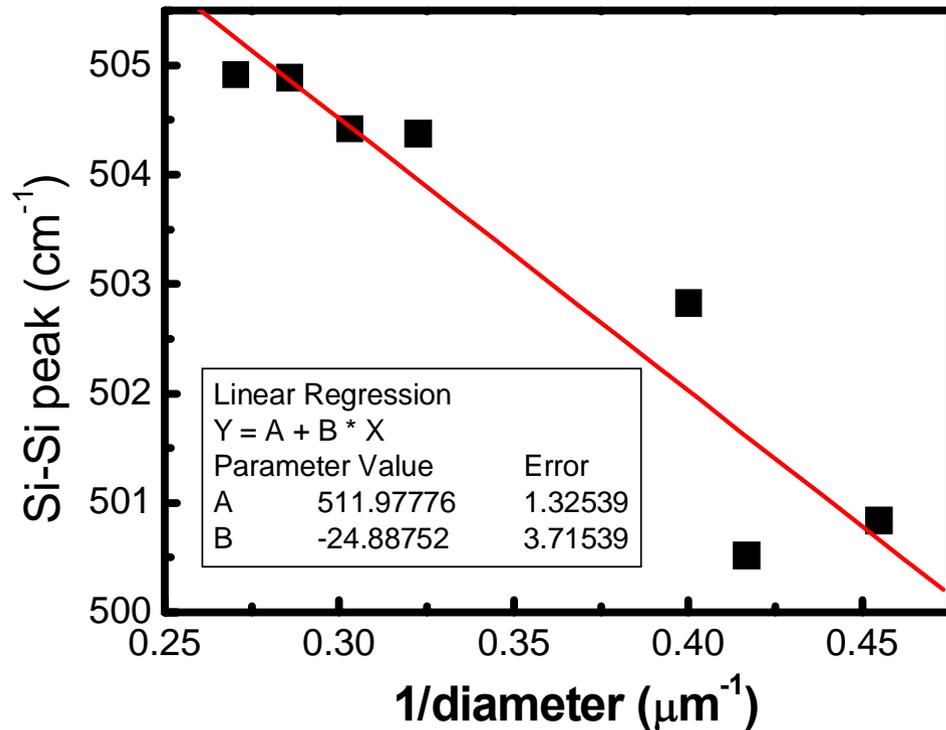
Sample 725



# Raman Spectra:



# Strain & 1/D

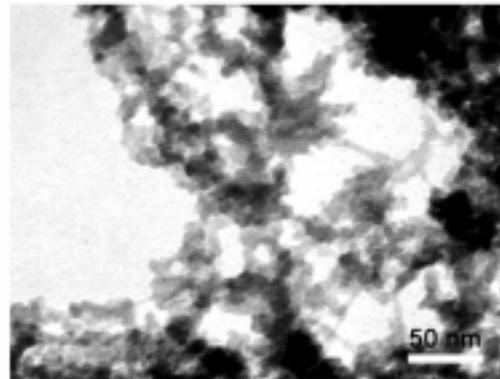


$$\omega_{Si-Si} = 520.5 - 62x - 815\varepsilon - C \cdot \frac{1}{D}$$

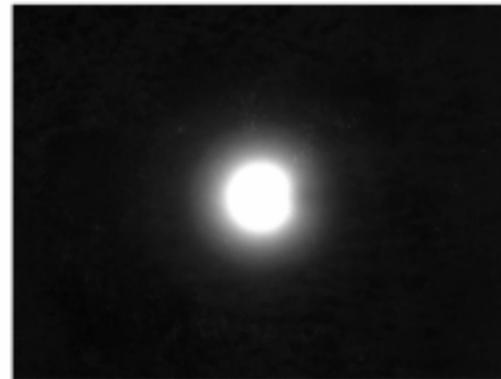
$C=24.89$



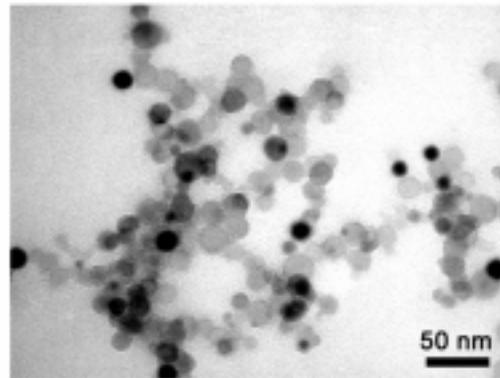
# Spherical Si Quantum Dots



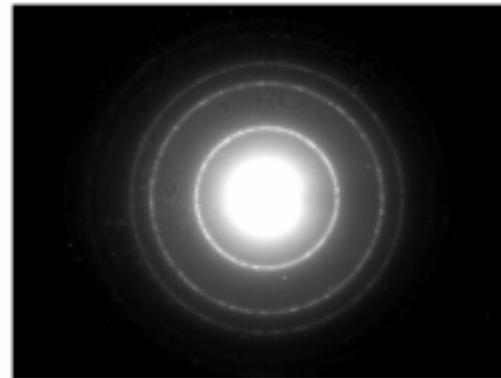
(a)



(b)



(c)



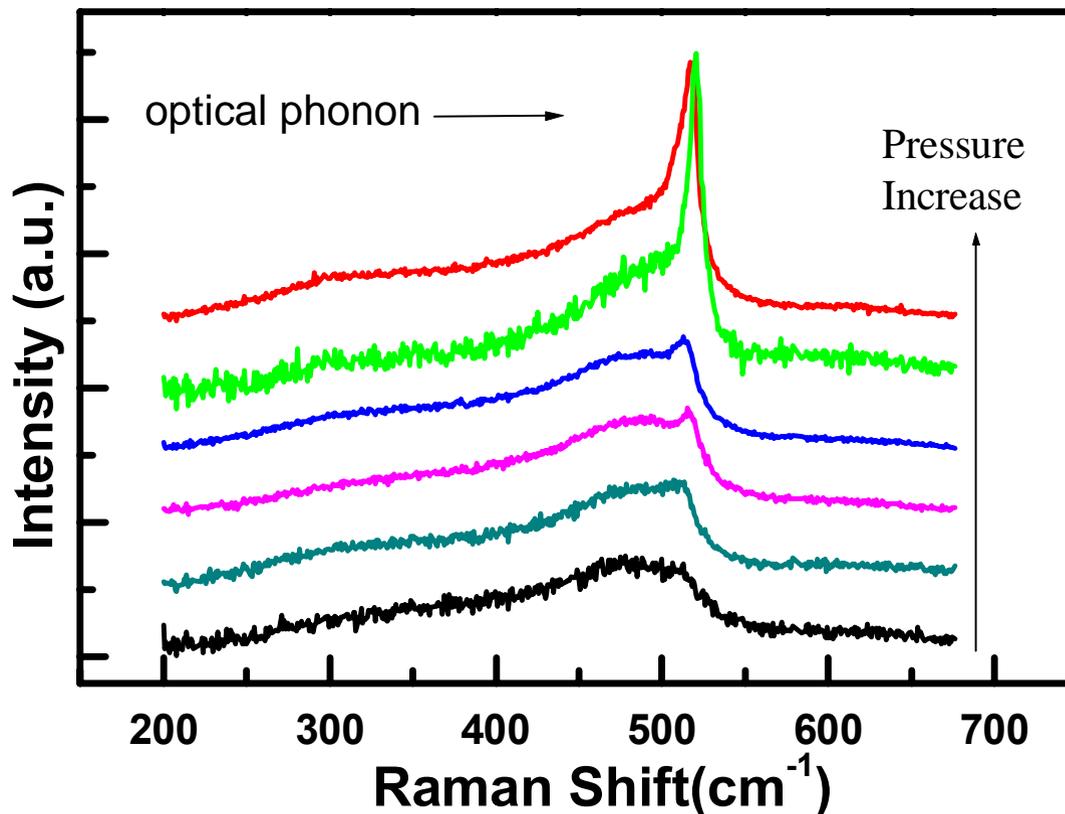
(d)

Y-C Liao, *et.al.*, Appl. Phys. Lett. 77, 4328 (2000).  
C-W Lin, *et.al.*, J. of Appl. Phys. 91, 1525 (2002).



# Raman Study of Si Dots' Size

Thermal Evaporation Growth Si Dots



D.-Y. Chien, *et.al.*, ICORS 2002

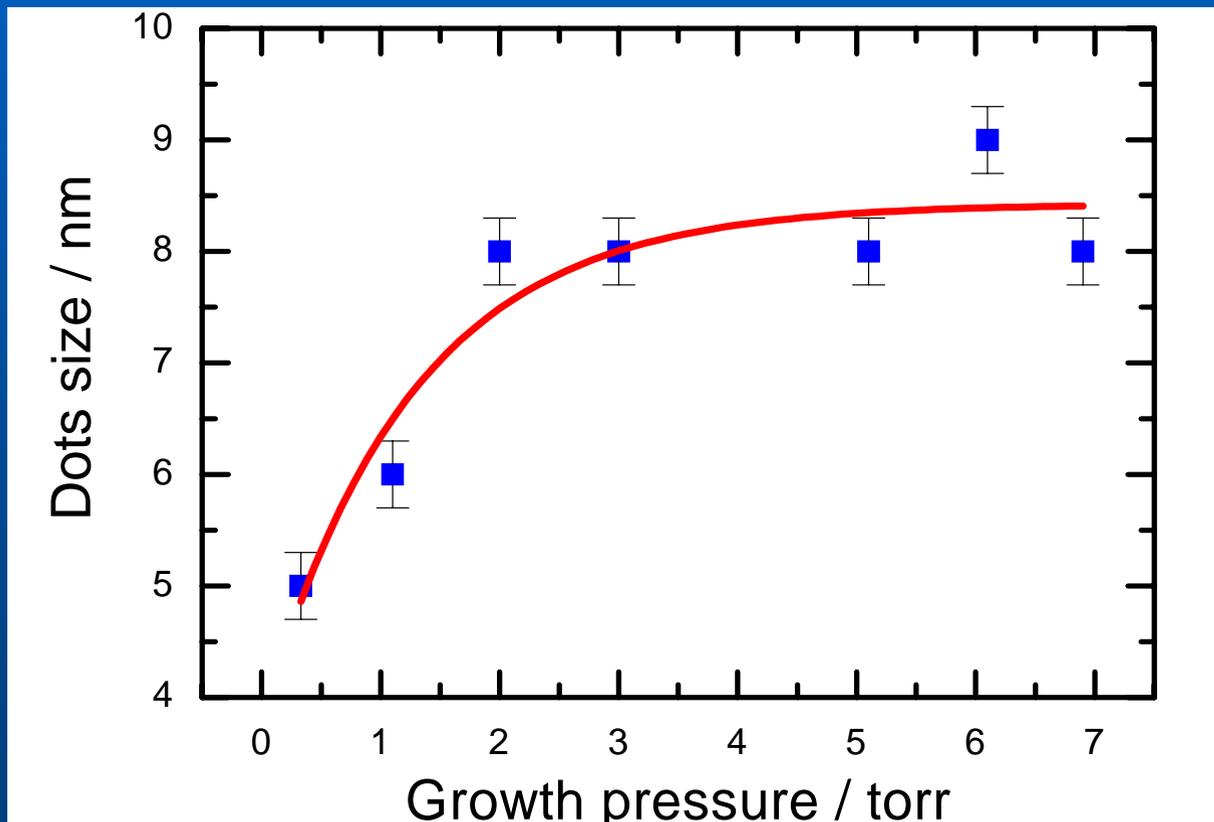


# Size of Dots:

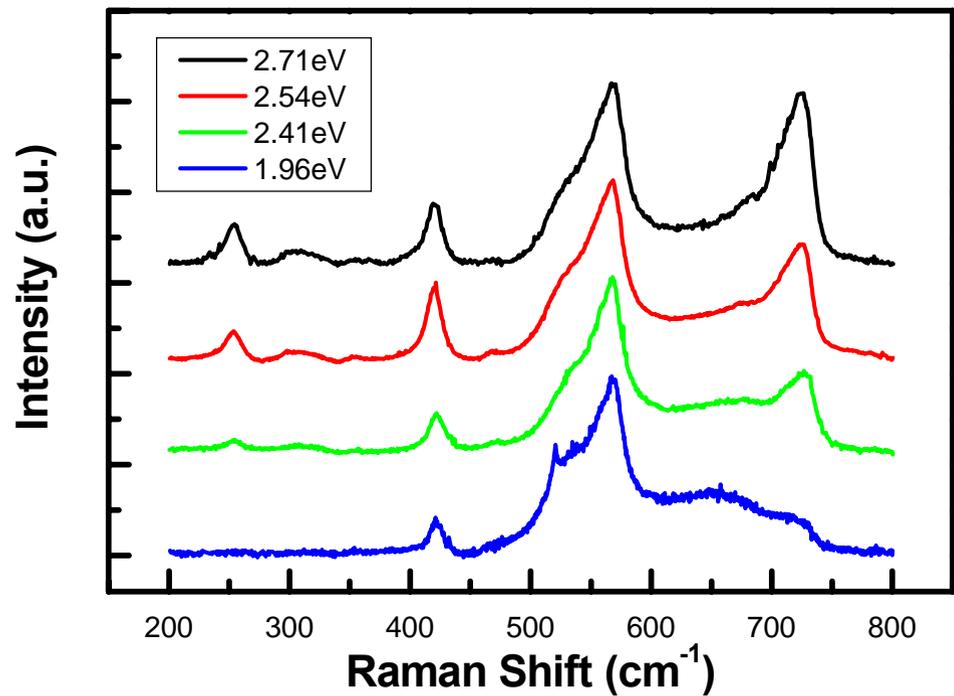
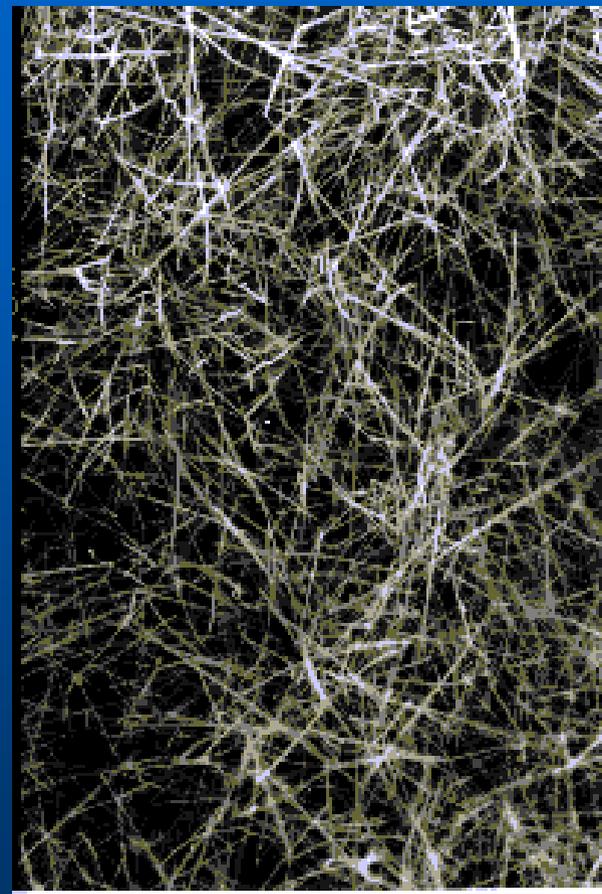
$$I(\omega) = \int_0^1 \frac{d^3 q |C(0, \vec{q})|^2}{[\omega - \omega(q)]^2 + (\Gamma_0 / 2)^2}$$

$$\omega(q) = [A + B \cos(\pi q / 2)]^{1/2}$$

$$|C(0, \vec{q})|^2 \cong e^{-q^2 L^2 / 4}$$

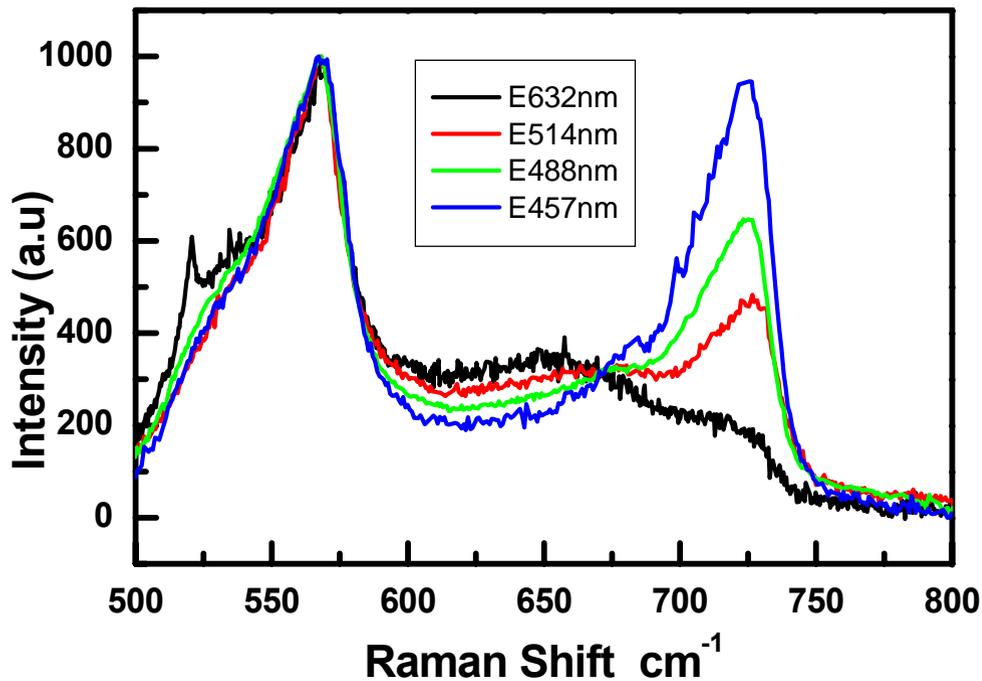


# Raman Spectra of GaN Wire



# LO-Phonon and Plasma Coupling

$$I(\omega) = \int_0^{q_{\max}} dq F(q) \cdot q^2 S(\omega, q) \operatorname{Im} \left( \frac{-1}{\varepsilon(\omega, q)} \right)$$



# CDF and IIF Mechanism

$$I(\omega) = \int_0^{q_{\max}} dq F(q) \cdot q^2 S(\omega, q) \operatorname{Im} \left( \frac{-1}{\varepsilon(\omega, q)} \right)$$

$$S_{CDF}(q, \omega) \propto (1 - e^{-\hbar\omega/k_B T})^{-1} \cdot \left( \frac{(\omega_{LO}^2 - \omega^2)}{(\omega_{TO}^2 - \omega^2)} \right)^2$$

$$S_{IIF}(q, \omega) \propto (1 - e^{-\hbar\omega/k_B T})^{-1}$$

$$F(q) = \left( \frac{4\pi}{q^2 + q_{FT}^2} \right)^2$$



# Coupled Dielectric Constant:

$$\varepsilon(q, \omega) = \varepsilon_{\infty} + \chi_{Phonon} + \chi_{Linhard}(q, \omega)$$

$$\chi_{Phonon} = \varepsilon_{\infty} \frac{\omega_{LO}^2 - \omega_{TO}^2}{\omega_{TO}^2 - \omega^2 - i\omega\gamma}$$

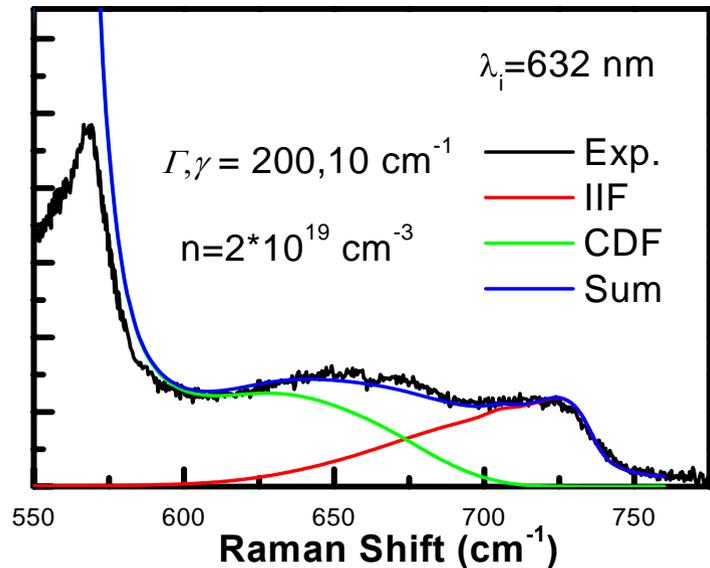
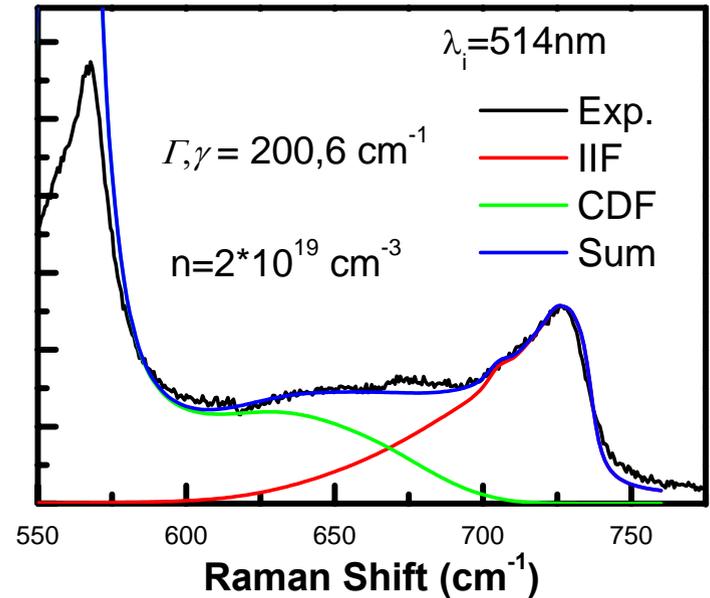
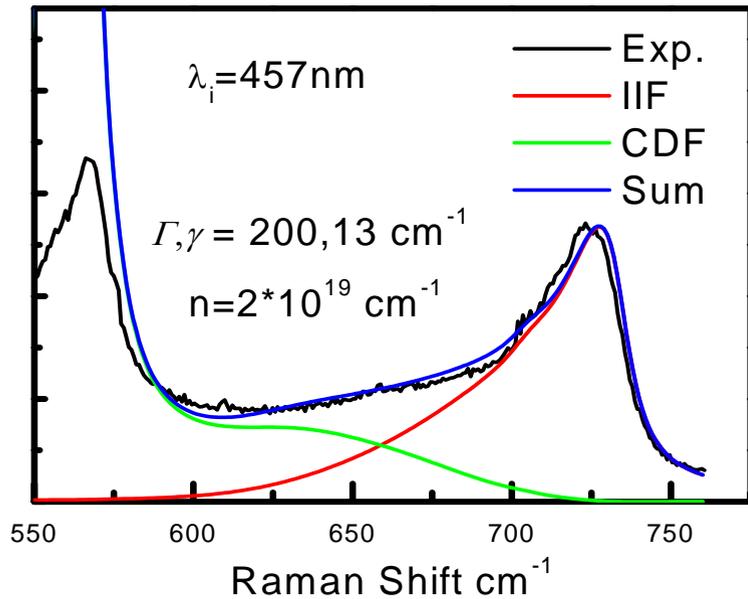
Lattice-Vibration Contributions

$$\chi_{Linhard}(q, \omega) = \frac{(1 - i\Gamma/\omega)[\chi^0(q, \omega + i\Gamma)]}{1 + (i\Gamma/\omega)[\chi^0(q, \omega + i\Gamma)/\chi^0(q, 0)]}$$

Plasma-Oscillation Contributions



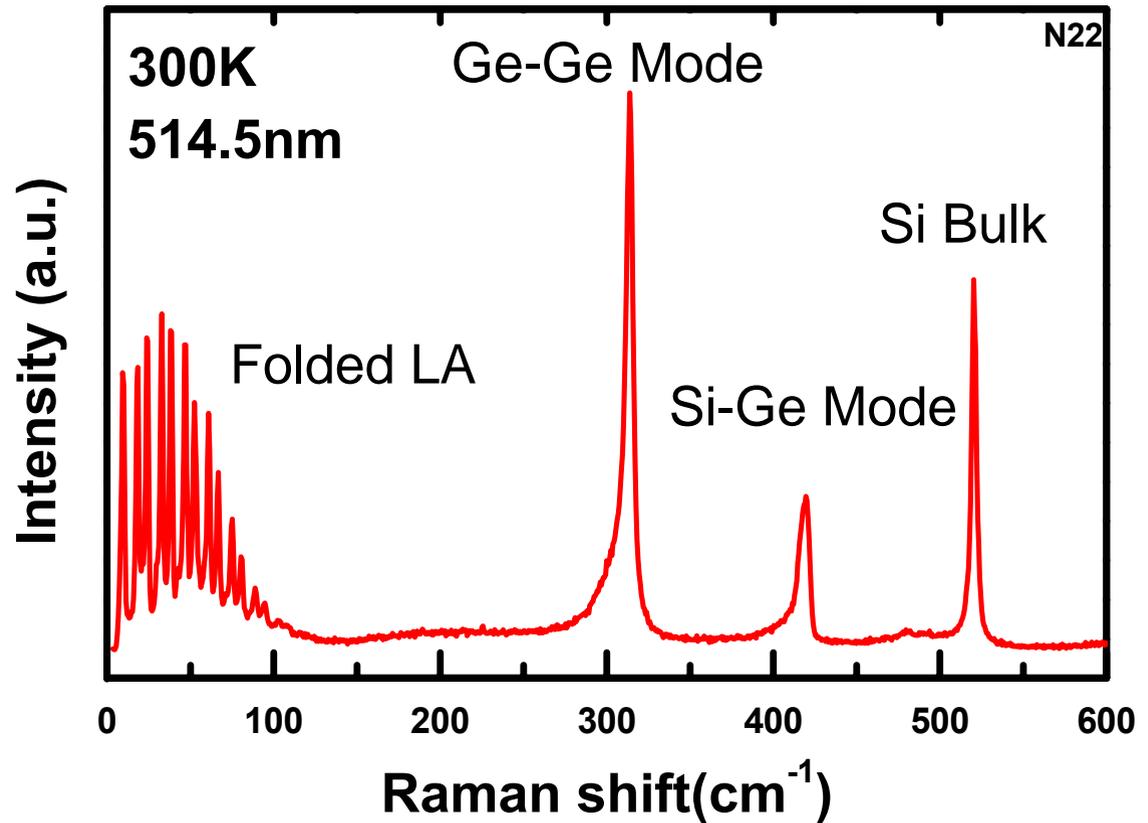
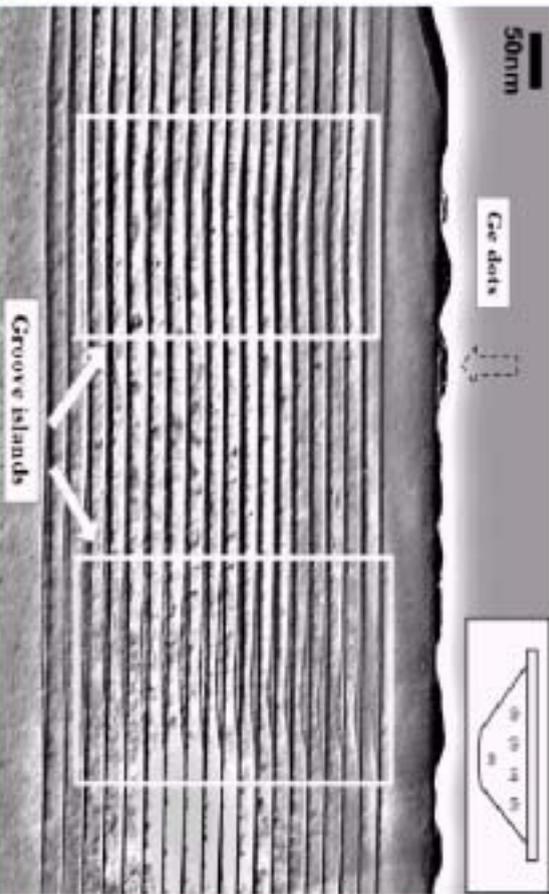
# Fitting Results



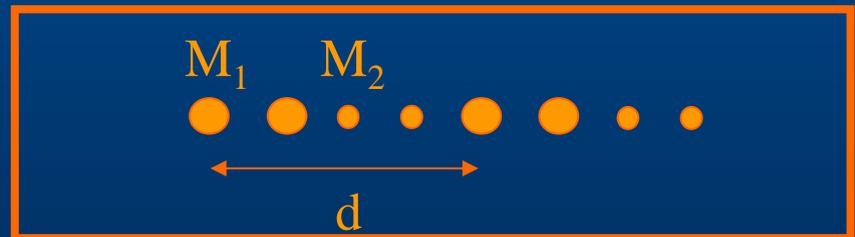
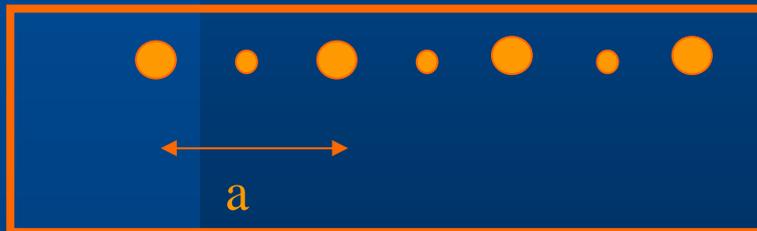
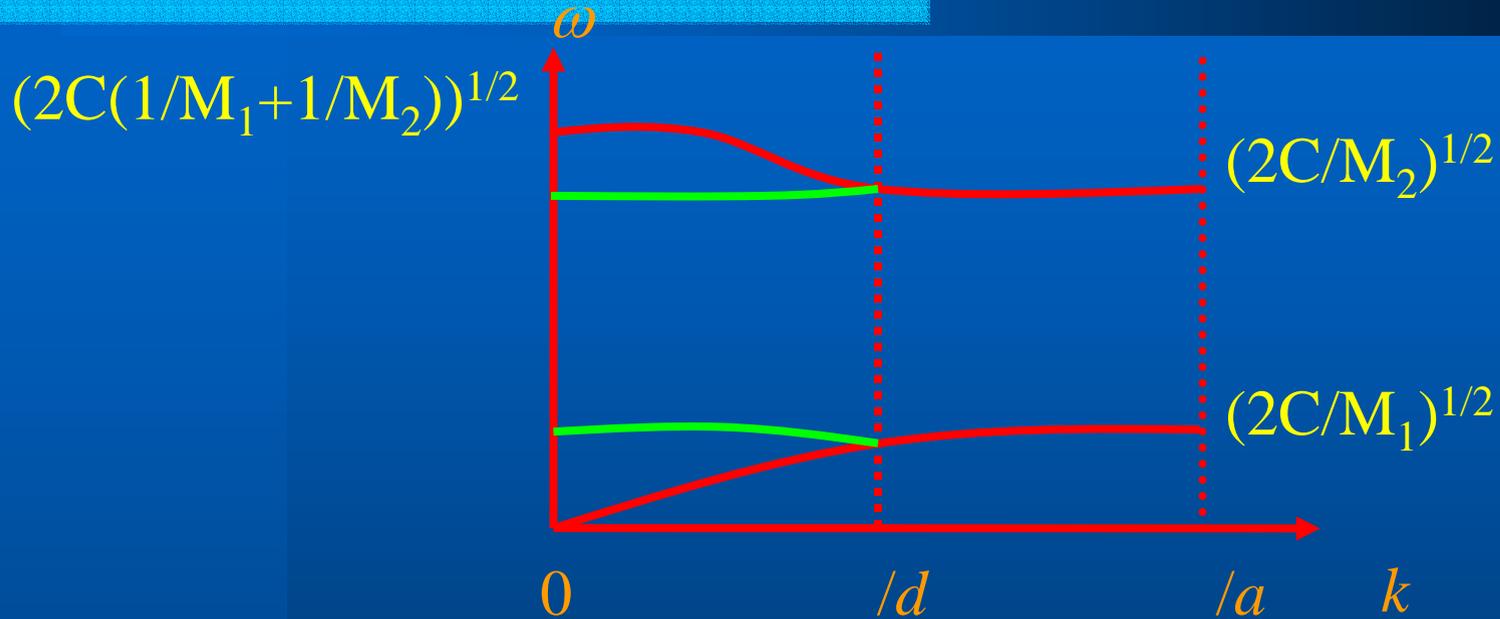
Heavy damping  $\Gamma = 200 \text{ cm}^{-1}$

Impurity Density:  $\sim 2 \cdot 10^{19} \text{ cm}^{-3}$

# Ge/Si MBE-Grown Superlattice

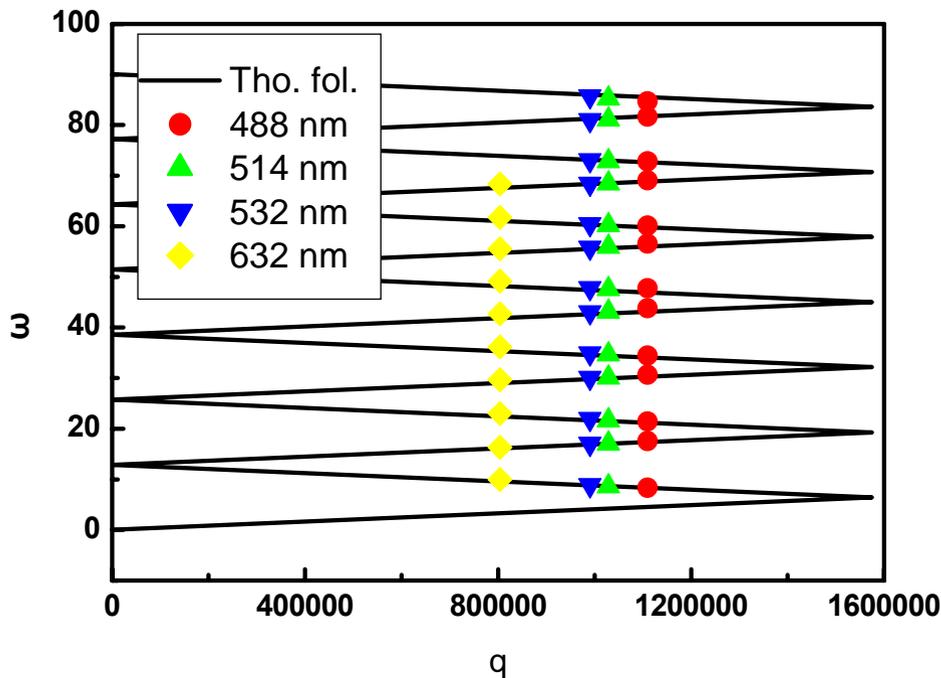


# Folded LA Phonon



# Thickness of Ge and Si layer

## Rytov theory

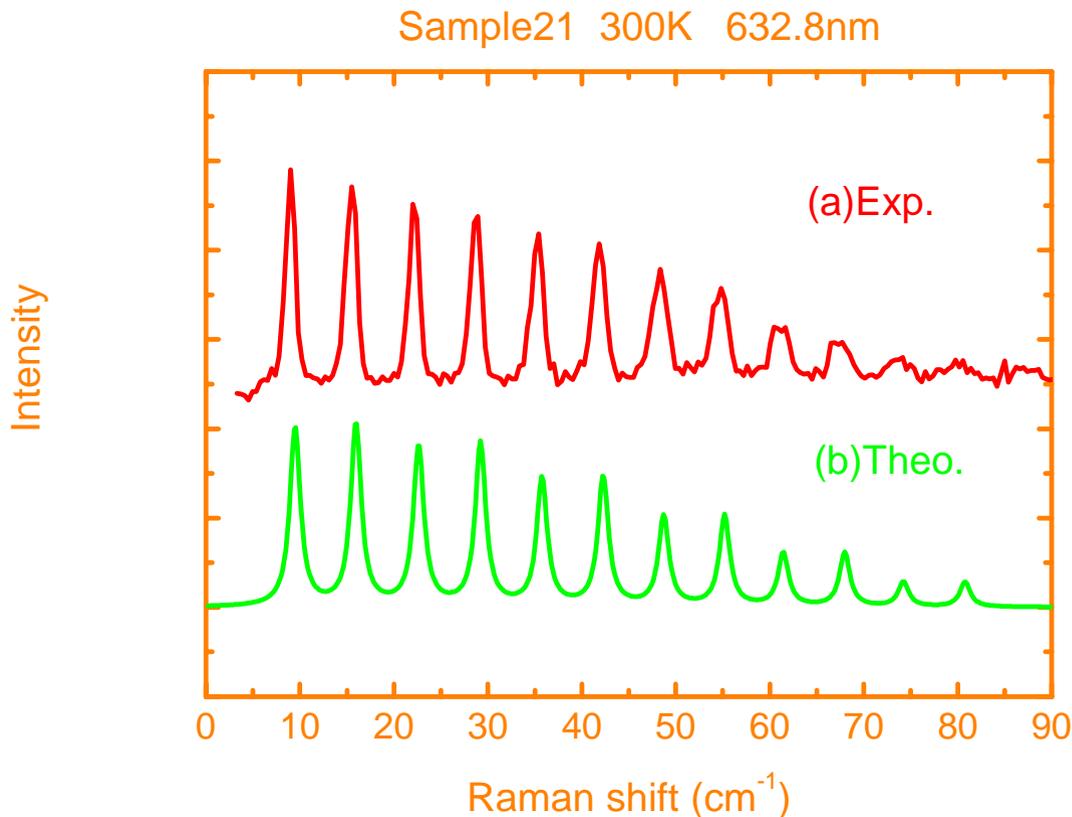


$$\omega = V_{SL} \left( \frac{2\pi m}{d} \pm q \right)$$



# Folded LA Intensity:

$$\frac{I_m}{I_{Brill}} = \frac{(P_b^{12} - P_a^{12})}{P_0^2} \frac{\sin^2(m\pi \frac{d_1}{d})}{\pi^2 m^2} \eta$$



$$\eta = \frac{\omega_m (n_m + 1)}{\omega_0 (n_0 + 1)}$$



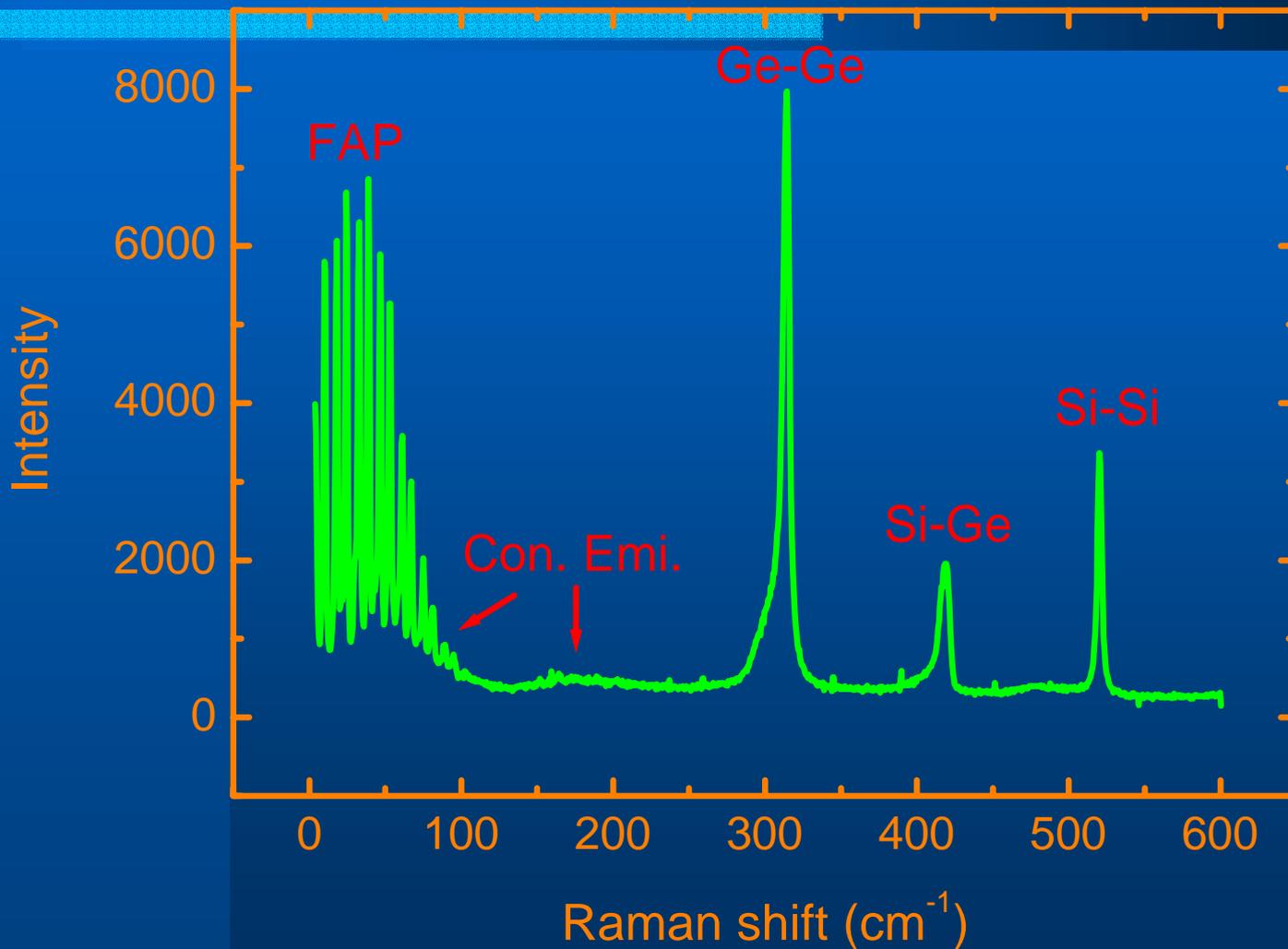
# Layer Thickness

樣品21	Si厚度 (nm)	Ge厚度 (nm)	厚度比 $d_1/d$	超晶格週期 $d$ (nm)
TEM圖	15±2	3±2	0.83	18±4
光譜擬合	17.5±0.6	2.40±0.08	0.88	19.9±0.7
樣品22				
TEM圖	17±2	2±2	0.90	19±4
光譜擬合	15.8±0.5	2.30±0.08	0.90	18.1±0.6
樣品23				
TEM圖	20±2	2±2	0.91	22±4
光譜擬合	19.6±0.7	2.50±0.09	0.89	22.1±0.8



# Continuous Emission:

Sample 22 300K 532nm Laser



# Theory of Continuous Emission:

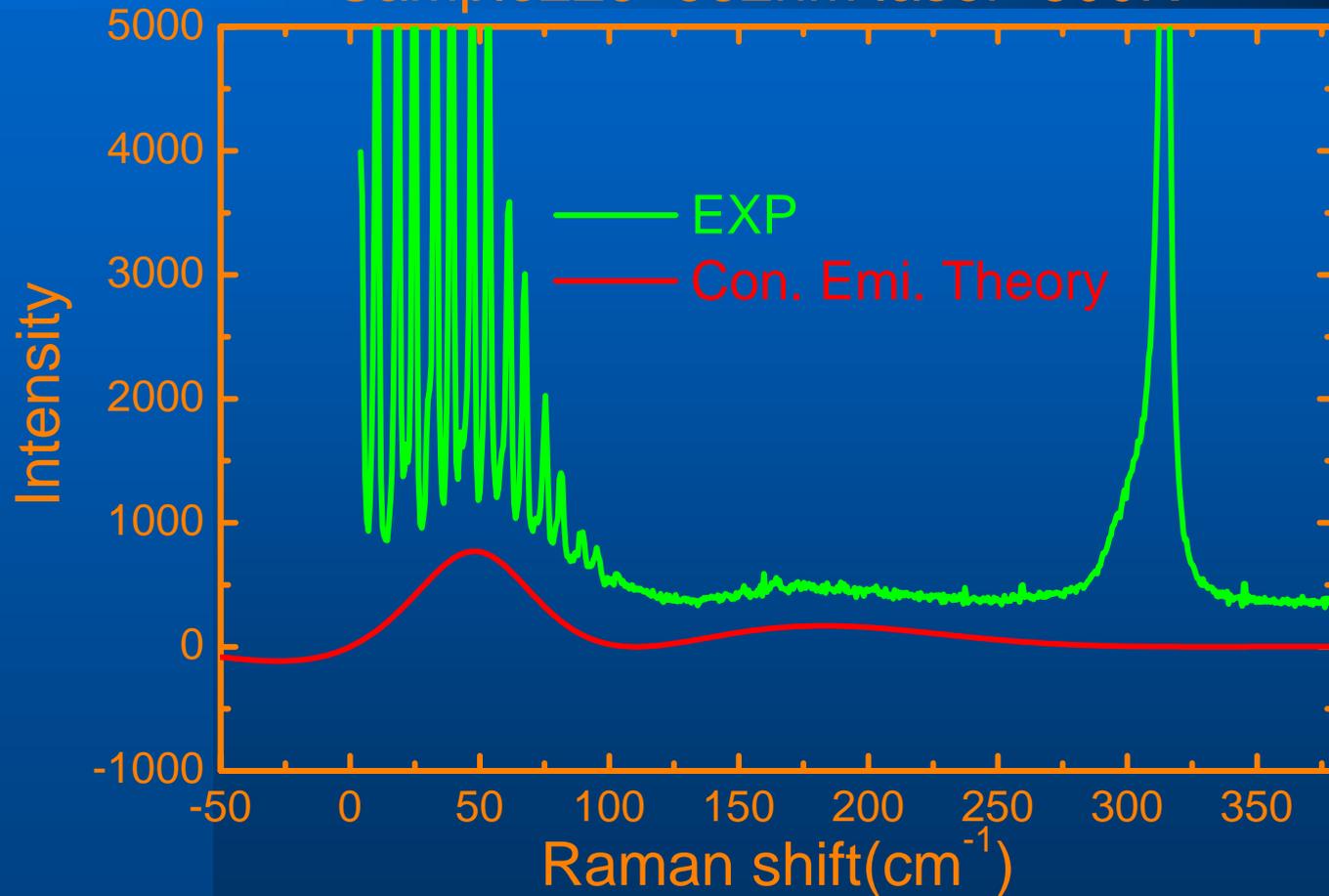
$$I_{(\omega)} \cong \sum_{q_z} \frac{q_z^2}{q_z} \frac{\sin^2 \frac{aq_z}{2}}{\left(\frac{aq_z}{2}\right)^2} \times (n_q + 1) \left( \omega - \omega_q \right)$$

$$\times \left| \sum_N \left( \Omega_N + i \frac{\gamma_e + \gamma_h}{2} \right)^{-1} \left( \Omega_N - \omega + i \frac{\gamma_e + \gamma_h}{2} \right)^{-1} \times \frac{4N^2}{4N^2 - \left(\frac{aq_z}{2}\right)^2} \right|^2$$



# Continuous Emission Fitting

Sample225 532nm laser 300K

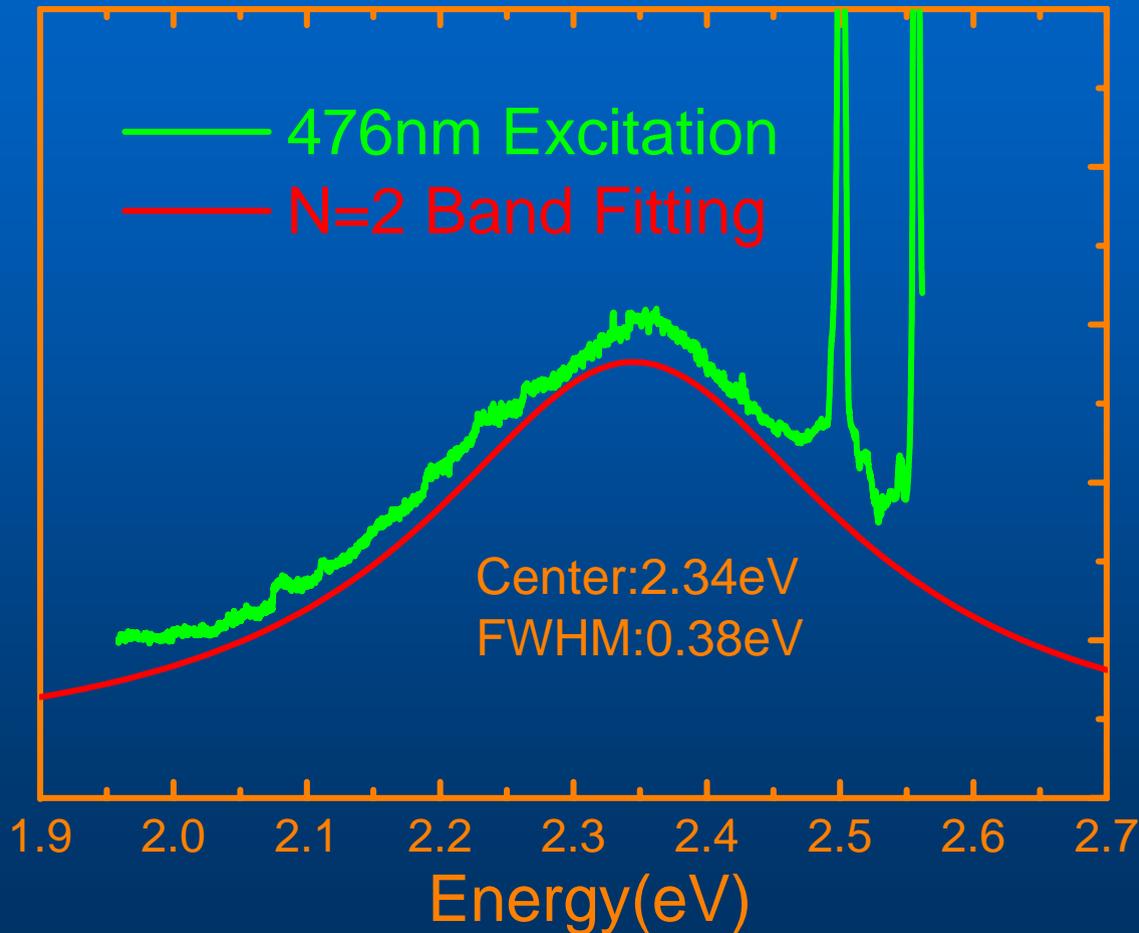


Resonant Energy : 2.34 eV



# Room Temperature Luminescence

Sample23 300K



# Summary:

## Visible Lasers + Raman Spectrometers

Can completely resolve the Physics properties of semiconductor from Raman-Phonon Lineshapes.

IF

Right energy laser

Good-resolution spectrometer



# 感謝Raman實驗室成員

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大學生：明峰、俊儀、旻宏

國中老師：吳奇穎、高祺俊



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清華：林諭男教授

台大：李嗣岑、鄭鴻祥、張玉明教授

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